

Application No. 10/712,108
Amendment dated February 7, 2007
After Final Office Action of December 27, 2006

Docket No.: 0941-0752P

AMENDMENTS TO THE CLAIMS

1. (Currently Amended) A pedestal supporting a substrate in a plasma chamber, comprising:
 - an insulating base comprising a recess;
 - a conductive layer comprising a bottom portion with a bottom width accommodated in the recess and an upper portion with an upper width not accommodated in the recess; and
 - a ceramic cover, comprising aluminum oxide, ~~at least partially covering closely surrounding the upper portion of the conductive layer with substantially no gap therebetween~~, the conductive layer being covered when the pedestal supports a substrate, wherein the ceramic cover is lower than the substrate.
2. (Previously Presented) The pedestal in claim 1, wherein the upper width is less than the bottom width and a diameter of the substrate.
3. (Cancelled)
4. (Original) The pedestal in claim 1, wherein the ceramic cover further overlies the insulating base.
5. (Original) The pedestal in claim 1, wherein the ceramic cover further comprises an opening exposing the conductive layer.

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6. (Previously Presented) The pedestal in claim 1, wherein the ceramic cover overlies the bottom portion of the conductive layer and further comprises a hollow portion accommodating the upper portion of the conductive layer.

7. (Original) The pedestal in claim 1, wherein the ceramic cover is ring-shaped.

8. (Original) The pedestal in claim 1, wherein the insulating base comprises silicon oxide.

9-10. (Cancelled)

11. (Currently Amended) A pedestal supporting a substrate in a plasma chamber, comprising:

an insulating base having a recess;

a conductive layer embedded in the recess; and

a ceramic cover, comprising aluminum oxide, overlying the insulating base and partially covering the conductive layer;

wherein

the conductive layer is covered when the pedestal supports a substrate;

the conductive layer further comprises an upper portion protruding from the recess; and

the ceramic cover is lower than the substrate when the pedestal supports the substrate;

and

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the ceramic cover closely surrounds the upper portion of the conductive layer with substantially no gap therebetween.

12. (Previously Presented) The pedestal in claim 11, wherein the upper portion is with a width less than the diameter of the substrate.

13. (Cancelled)

14. (Previously Presented) The pedestal in claim 11, wherein the ceramic cover further comprises a hollow portion accommodating the upper portion of the conductive layer.

15. (Previously Presented) The pedestal in claim 11, wherein the ceramic cover further comprises a hollow portion accommodating the upper portion of the conductive layer and exposing the upper portion of the conductive layer.

16. (Original) The pedestal in claim 11, wherein the ceramic cover is ring-shaped.

17. (Original) The pedestal in claim 11, wherein the insulating base comprises silicon oxide.

18-19. (Cancelled)

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20. (Previously Presented) A pedestal supporting a substrate in a plasma chamber, comprising:

a silicon-oxide base having a recess;

a titanium layer having a bottom portion embedded in the recess, and an upper portion, narrower than the bottom portion and the substrate, protruding from the recess; and

a ring-shaped ceramic cover, comprising aluminum oxide and having a hollow portion accommodating the upper portion of the titanium layer therein, overlying the silicon-oxide base and a portion of the bottom portion of the titanium layer;

wherein the titanium layer is covered when the pedestal supports the substrate; and

the ceramic cover is lower than the substrate when the pedestal supports the substrate.

21. (Previously Presented) The pedestal as claimed in claim 20, wherein the hollow portion of the ceramic cover further exposes the upper portion of the titanium layer.

22. (Cancelled)

23. (New) The pedestal in claim 11, wherein the conductive layer further comprises a bottom portion, and the width of the upper portion is less than the width of the bottom portion.